IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PATENT APPLICATION

Applicant: Chae, et al. Case: APPM/8501/ETCH/DRIE

Serial No.: 10/706,902 Filed: November 11, 2003

Examiner: **Tran, Binh X.** Group Art Unit: **1765**

Conf. No.: **7748**

Title: SELECTIVE ETCH PROCESS OF A SACRIFICIAL LIGHT ABSORBING

MATERIAL (SLAM) OVER A DIELECTRIC MATERIAL

Mail Stop: AMENDMENT Commissioner for Patents P.O. Box 1450

Alexandria, VA 22313-1450

RESPONSE TO OFFICE ACTION DATED FEBRUARY 2, 2006

SIR:

In response to the Office Action dated February 2, 2006, having a shortened statutory period for response expired on May 2, 2006, please enter this Response and reconsider the claims pending in the application for reasons discussed below. The Applicants believe that a \$250 excess claim fee is due in connection with this response. The Commissioner is hereby authorized to charge counsel's Deposit Account No. 50-3562 for this fee, and for any other fees, including extension of time fees or additional excess claims fees, required to make this response timely and acceptable to the Office.